

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/553,675	10/31/2005	Satoshi Takei	125640	1819
200	7590 04/27/2007		EXAMINER	
OLIFF & BERRIDGE, PLC P.O. BOX 19928 ALEXANDRIA, VA 22320		-	DEO, DUY VU NGUYEN	
			ART UNIT	PAPER NUMBER
			1765	
	•			
SHORTENED STATUTOR	Y PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE	
3 MO	NTHS	04/27/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

	r	
dress		
D) DAYS,		
mmunication.		
	i	
•		
merits is		
er.		
R 1.121(d). O-152.		
Stage		
-		

			ι
	Application No.	Applicant(s)	
	10/553,675	TAKEI ET AL.	
Office Action Summary	Examiner	Art Unit	
	Duy-Vu N. Deo	1765	
The MAILING DATE of this communication Period for Reply	appears on the cover sheet wit	th the correspondence address	
A SHORTENED STATUTORY PERIOD FOR REWHICHEVER IS LONGER, FROM THE MAILING - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory per - Failure to reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the material patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNIC 1.136(a). In no event, however, may a re- tiod will apply and will expire SIX (6) MON- tute, cause the application to become ABA	CATION. ply be timely filed I'HS from the mailing date of this communication. ANDONED (35 U.S.C. § 133).	
Status	•		
1) Responsive to communication(s) filed on 12	7 October 2005.		•
· <u> </u>	his action is non-final.		
3) Since this application is in condition for allow	·	•	
closed in accordance with the practice unde	er <i>Ex par</i> te <i>Quayle</i> , 1935 C.D.	11, 453 O.G. 213.	
Disposition of Claims			
4) Claim(s) 1-13 is/are pending in the application 4a) Of the above claim(s) is/are without 5) Claim(s) is/are allowed. 6) Claim(s) 1-13 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and	drawn from consideration.		
9) The specification is objected to by the Exam	iner.		
10)⊠ The drawing(s) filed on <u>17 October 2005</u> is/a	are: a)⊠ accepted or b)□ ot	ejected to by the Examiner.	
Applicant may not request that any objection to t	he drawing(s) be held in abeyan	ce. See 37 CFR 1.85(a).	
Replacement drawing sheet(s) including the corn 11) The oath or declaration is objected to by the		· ·	
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for fore a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the p application from the International Burn * See the attached detailed Office action for a l	ents have been received. ents have been received in Apriority documents have been received in Apriority documents have been reau (PCT Rule 17.2(a)).	oplication No received in this National Stage	
Attachment(s)			
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date 12/19/05.	Paper No(s)	ummary (PTO-413) /Mail Date formal Patent Application 	

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- 2. Claims 1, 3-13 are rejected under 35 U.S.C. 102(a) as being anticipated by Uenishi (JP 2002-081328).
- U.S. Patent Application 10/392,814 claims a foreign priority to the JP 2002-081328. Therefore, it is considered to be the correct translation of the JP application.

Uenishi describes a method for forming resist pattern comprising forming an intermediate layer on a substrate, heating the intermediate layer, forming a photoresist layer on the intermediate layer, exposing and developing the photoresist layer to form a pattern, etching the intermediate layer corresponding to the pattern of the photoresist layer (paragraphs 0188-0193). The intermediate layer is made from polymer, solvent, azo initiators (claimed blowing group), and organic materials (paragraphs 0033, 0057-0061, 0165). Therefore, this would form claimed porous underlayer coating made from a blowing agent or polymer having a blowing group, organic material, and a solvent.

Referring to claims 7 and 8, the composition described above would decomposed when heated to generate nitrogen, carbon dioxide, or water vapor since they make up of the same chemical as that of claimed invention.

Application/Control Number: 10/553,675 Page 3

Art Unit: 1765

Referring to claims 9-12, the crosslink compounds contain 3-5 benzene rings per molecule (paragraph 0061).

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claim 2 is rejected under 35 U.S.C. 103(a) as being unpatentable over Uenishi as applied to claim 1 above, and further in view of Adams et al. (US 2002/0172896).

Referring to claim 2, Uenishi doesn't explicitly describe forming an antireflective layer before or after forming the intermediate layer. However, at the time of the invention using an antireflective layer for a photoresist process is well known to one skilled in the art. Adams teaches using an antireflective layer during a photoresist process (paragraphs 0009, 0074-0077). One skilled in the art would find it obvious in light of Adams' teaching to use an antireflective layer because it would reduce the problem of reflected radiation between the substrate and the photoresist layer as taught by Adams (paragraph 0009). It is obvious that the antireflective layer can be formed either before or after forming the intermediate layer as long as it is formed between the photoresist and the substrate.

Art Unit: 1765

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Duy-Vu N. Deo whose telephone number is 571-272-1462. The examiner can normally be reached on Mon-Fri.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Duy-Vu N Deo Primary Examiner Art Unit 1765

4/25/07